

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

BAKKER et al.

Application No.: TO BE ASSIGNED

Group Art Unit: UNKNOWN

Filed: November 21, 2003

Examiner: UNKNOWN

Title: LITHOGRAPHIC PROJECTION APPARATUS WITH MULTIPLE  
SUPPRESSION MESHES

\* \* \* \*

November 21, 2003

**INFORMATION DISCLOSURE STATEMENT**

MAIL STOP PATENT APPLICATION

Commissioner for Patents

P.O. BOX 1450

Alexandria, VA 22313-1450

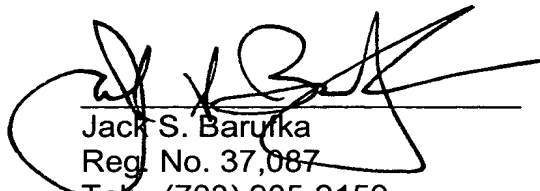
Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully submitted,

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FC-PAT-1449 (modified)  
 To: U.S. Department of Commerce  
 (PW FORM PAT-1449)  
 Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306794	P-0388.010-US

# **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

Applicant: BAKKER et al.	
Appln. No.: TO BE ASSIGNED	
Filing Date: November 21, 2003	
Examiner:	Group Art Unit:

Date: November 21, 2003 Page 1 of 1

## **U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					
	OR					

## **FOREIGN PATENT DOCUMENTS**

		Document Number	Date MM/YYYY	Country	Inventor Name	Abstract		Readily Available	
						Enclosed	No	Enclose	No
	PR	EP 1 182 510 A1	02/2002	Europe	MOORS et al.	X			
	QR								
	RR								
	SR								
	TR								
	UR								
	VR								

## **OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," <i>J. Vac. Sci. Technol. B</i> 12(6):3833-3840, XP-002096163 (1994)				
XR					
YR					
ZR					
AAR					
BBR					
CCR					

Examiner Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.